

Laurel 5.1x
Mailbox empty at 10:08
User {Brotz.PA}

Thursday April 3, 1980 10:09 am PST
366 free disk pages
New mail Mail file {RunA26Z68} Quit

↑
Table of Contents Area
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▶	9 Apr. 3	To: @Process57.NMos	1.8 Measure t-ox on test wafer first ox and send to C-V processing and test.
	10 Apr. 3	To: @Process57.NMos	1.9 Continue test wafer Si3N4, hold test wafer field, test wafer field ox.
	11 Apr. 3	To: @Process57.NMos	1.10 Pre-nitride clean.
+	12 Apr. 3	To: @Process57.NMos	1.11 Si3N4 deposition. 700 Angstroms.
	13 Apr. 3	To: @Process57.NMos	2.1 Mask #1, field mask. Negative resist lithography.
	14 Apr. 3	To: @Process57.NMos	2.1b Inspection of lithographic results.
	15 Apr. 3	To: @Process57.NMos	2.2 Etch nitride in E1 plasma. (Dry

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Displayed Message Area
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Display Hardcopy Delete Undelete Move to {RunA26Z68}

Subject: 1.8 Measure t-ox on test wafer first ox and send to C-V processing and test.
To: @Process57.NMos

Test wafer first ox.

Operator: Brotz
Start time: April 3, 1980 9:54 am PST
Finish time: April 3, 1980 10:31 am PST

Record t-ox: 345

Record V-t: 0.56

End of Message.

↑
Composed Message Area
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New form Answer Forward Get, Put {} Deliver

Subject: 1.11 Si3N4 deposition. 700 Angstroms.
To: @Process57.NMos

Operator: **■Name■**
Start time: **■time■**
Finish time: **■time■**

Test wafer Si3N4.

Record t-Nitride: **■value■**
Record n-Nitride: **■value■**

End of message.

Figure 2. Standard Laurel Display Screen